



Development and properties of 100 mm-square size LTCC-GEM

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1-1. Introduction

● Motivation : on-site non-destructive inspection

- Long-term field operation
- Sealed gas detector
- Reliable GEM

● Breakdown of GEM due to discharge

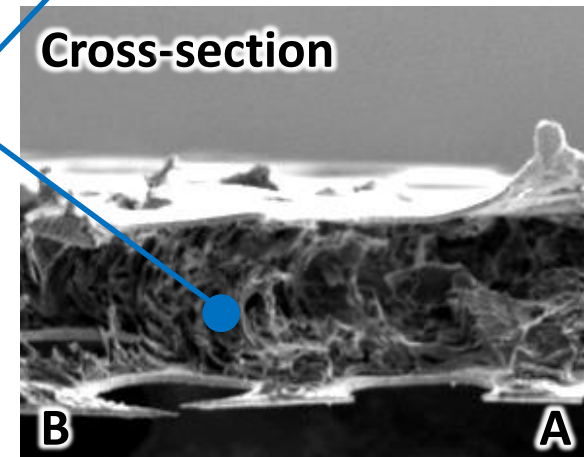
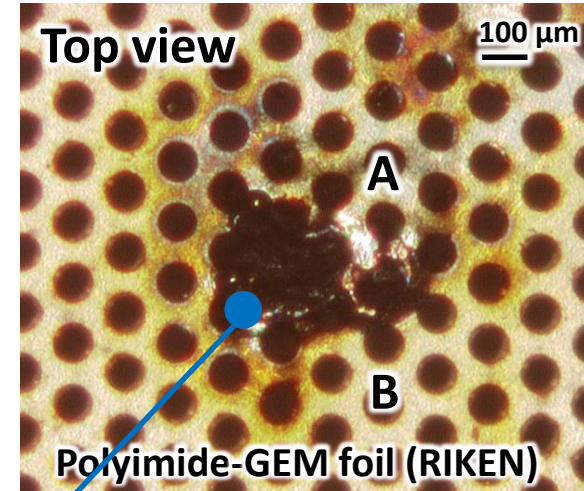
PI- and LCP-GEM “sometimes” breakdown due to discharge at high gain and never recover.

● Identify the cause

- Analyzed around the burn section with SEM-EDX
- The insulator layer changed into the porous body and carbonized

● Purpose of our study

Development of a reliable GEM against discharge
→ We select new materials for the insulator.



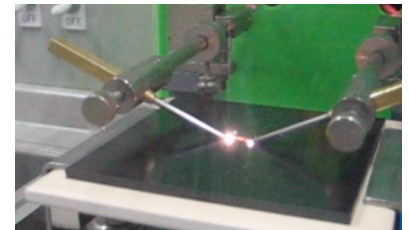
1-2. Candidate of insulator materials

Materials	Our Study			
	PI (Polyimide)	LCP (Liquid Crystal Polymer)	PTFE (Teflon™)	LTCC (Low Temperature Co-fired Ceramics)
Volume resistivity [$\Omega \cdot \text{cm}$]	10^{17}	6×10^{16}	$> 10^{18}$	$> 10^{14}$
Arc resistance [sec]	135	186	> 300	> 300
Melting point [degree C]	800	450	327	> 800
Density [g/cm^3]	1.43	1.35	2.13~2.2	~3
Dielectric Constant	~3.4	~3.5	2.1	~7.5

- Carbonization begins when arc-discharge occurs.

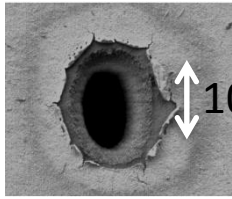
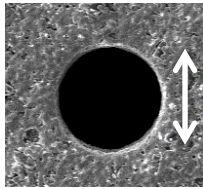
- We gave our attention to “arc resistance[†]”.

† The time period of the material resists the formation of surface-conduction path based on ASTM D 495 standard




- PTFE and LTCC show higher arc-resistance than PI and LCP.

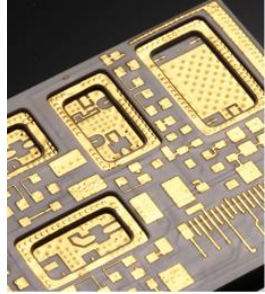
1-3. Prototype of PTFE- and LTCC-GEM

	PTFE-GEM	LTCC-GEM
Test size	20 mm x 20 mm	10 mm x 10 mm
GEM thickness	50 μm	100 μm
Drilling holes	Laser	Punch
Hole shape	 100 μm	 100 μm
The maximum gain	$> 10^4$	$> 10^4$
Number of discharges	$> 10^4$ No breakdown	$> 10^4$ No breakdown
reference	3rd MPGD(2013), Tamagawa+	4th MPGD(2015), Komiya+

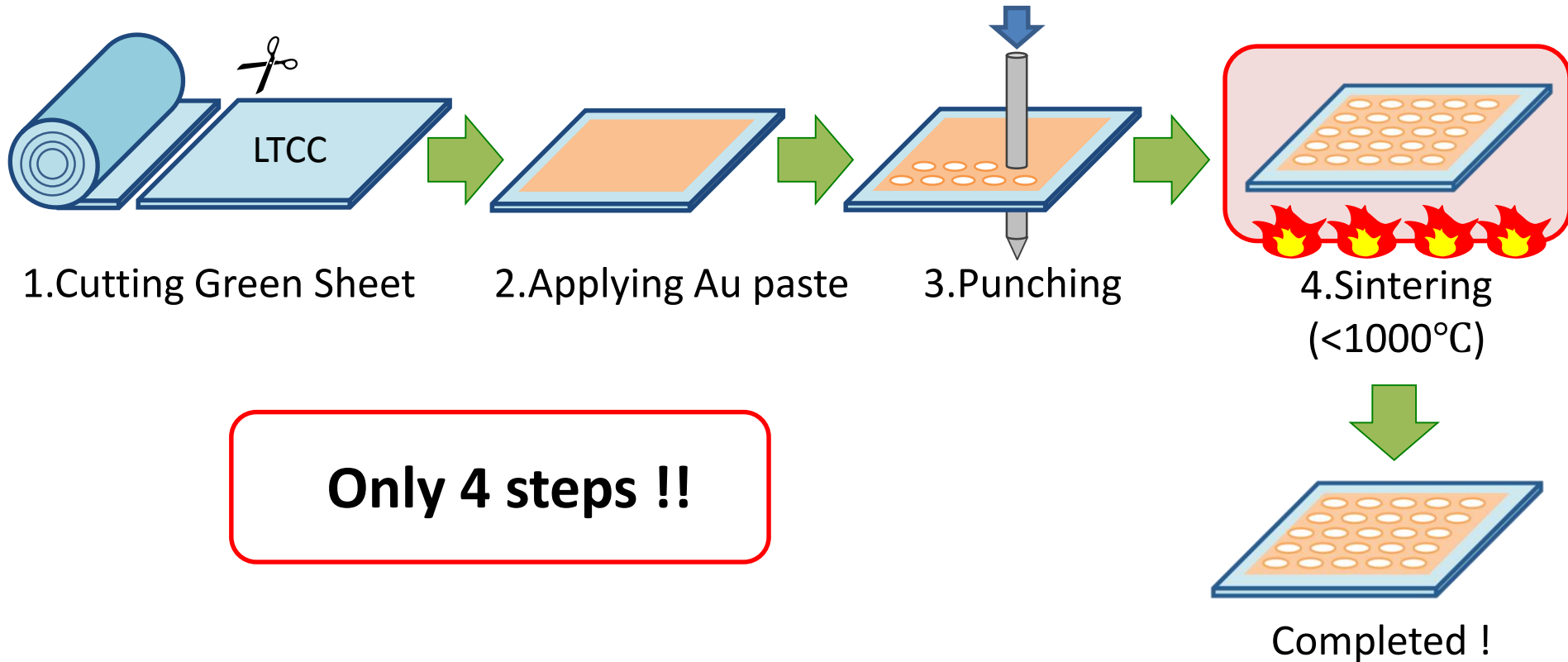
- We succeeded to fabricate both GEMs.
- LTCC-GEM is better hole shape and ease to drill than PTFE-GEM.
- We selected **LTCC-GEM** to study in detail.

1-4. Fabrication process of LTCC-GEM

- Manufactured by Hirai Seimitsu Kogyo Corporation, Japan  [HIRAI](#)
- Used for highly integrated circuits which embed electric parts



Process



1-5. Advantages of LTCC-GEM

LTCC-GEM (10 mm-sq. size) has 3 great advantages!

✧ Good operation

- High gain : $\sim 10^4$ @ $\Delta V_{\text{GEM}} = 760 \text{ V}$
- Discharge tolerance : Although $>10^4$ discharges, No breakdown

✧ Easy to handle

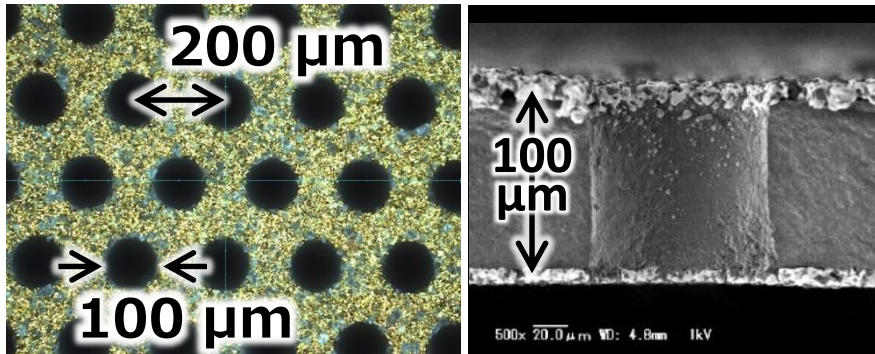
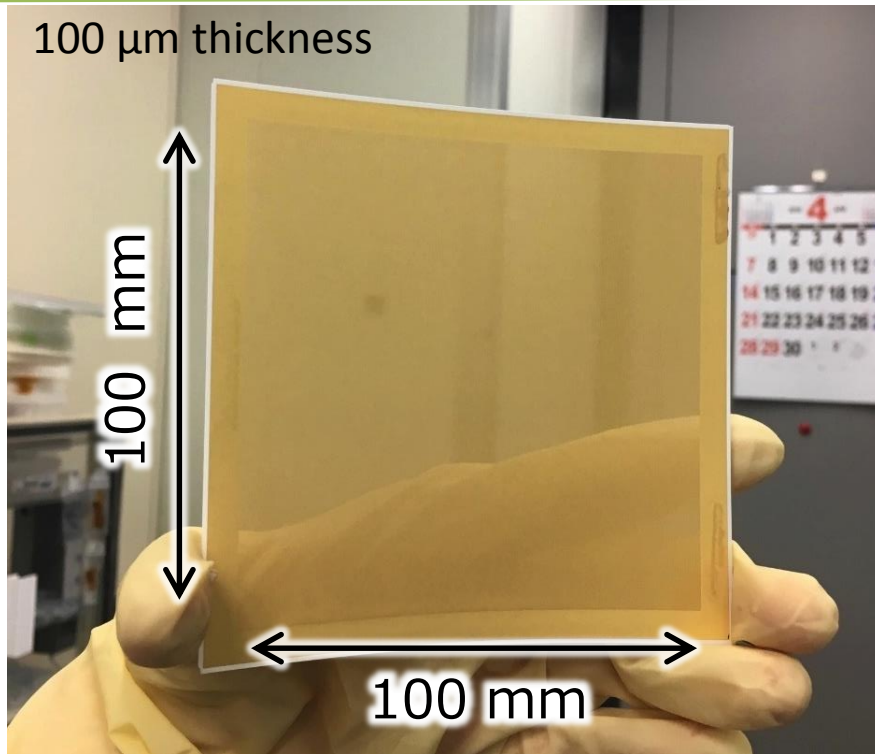
- Rigid structure
- Low outgassing (since LTCC is an inorganic material)

✧ Simplified fabrication process

- Cost-effective
- Flexibility of GEM in a desired size and shape (mask less)

In this talk, we report fabricating **LTCC-GEM** of **100 mm-square** size!

2-1. LTCC-GEM of 100 mm-sq. size



Substrate : 125 mm x 125 mm

Eff. Area : 100 mm x 100 mm

Hole Pitch : 200 μm

Hole size : ϕ 100 μm

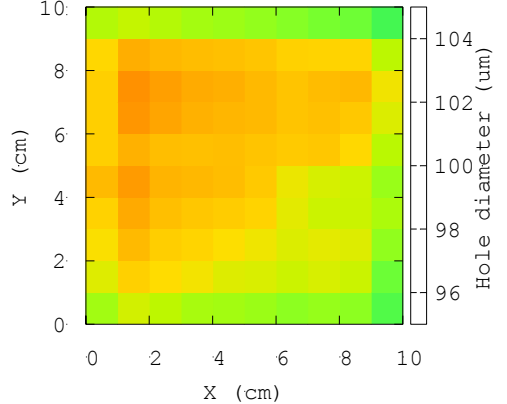
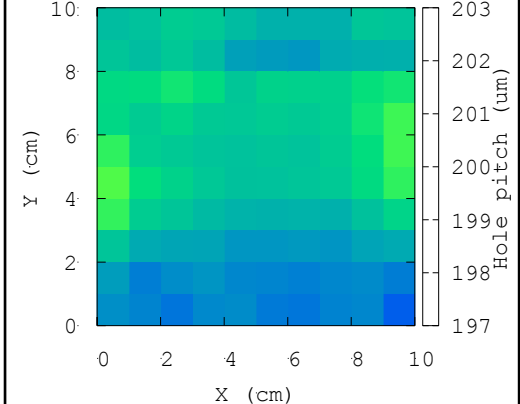
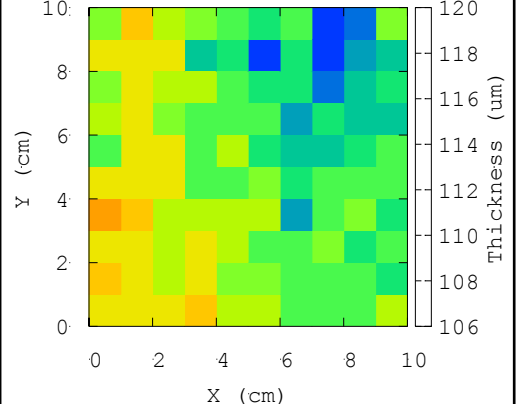
Thickness : 100 μm (this work)
200 μm
(In detail, see Kato's poster#6)

Electrode : Gold (Au)

Resistance : $\sim 160 \text{ G}\Omega$ @ 300 V

COST : $\sim \text{€}800$

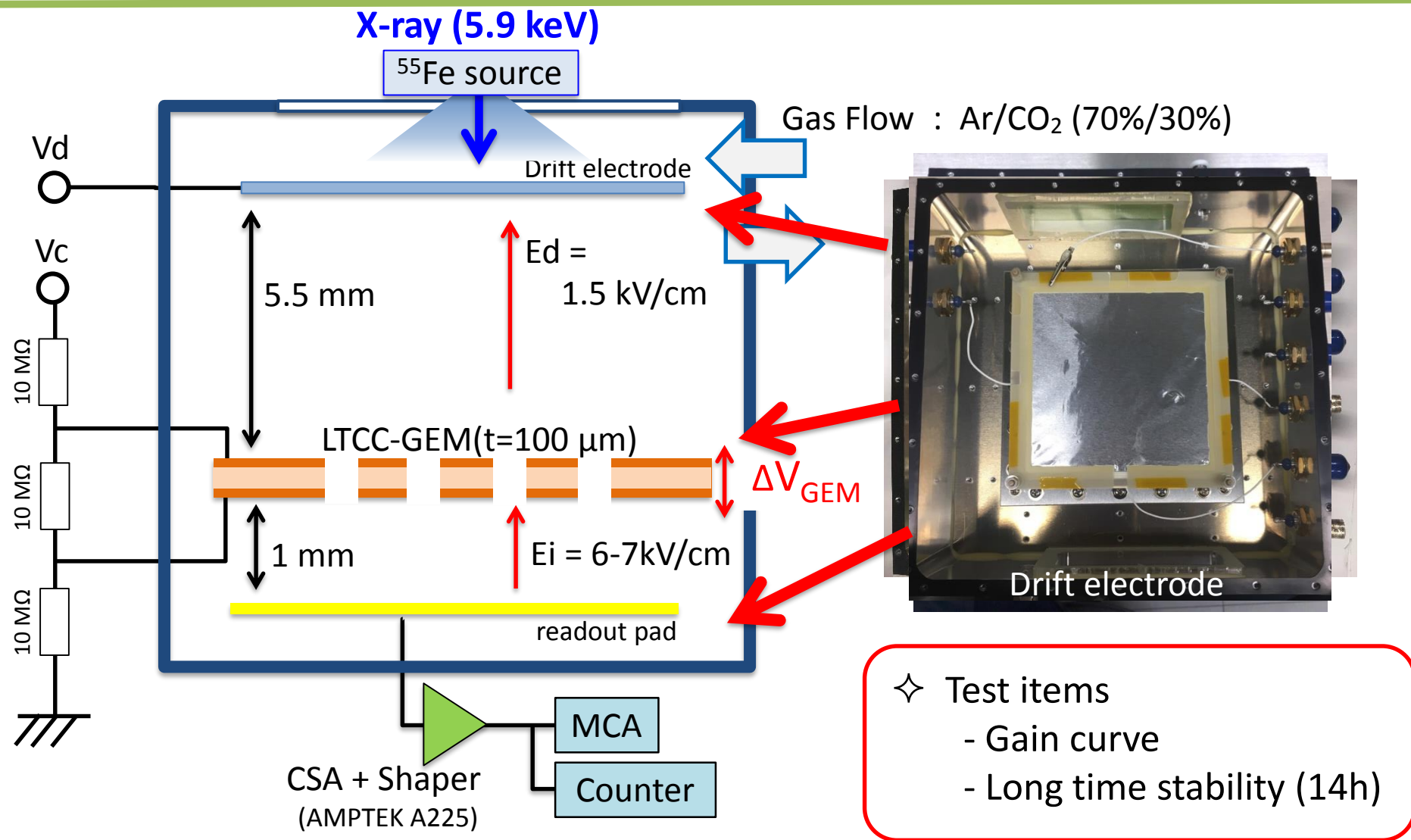
2-2. Mechanical accuracy

	Hole diameter	Hole pitch	Thickness
Design	$\Phi 100 \mu\text{m}$	$200 \mu\text{m}$	$100 \mu\text{m}$
Measured Average	$101.5 \pm 3.2(1\sigma) \mu\text{m}$	$198.6 \pm 5.1(1\sigma) \mu\text{m}$	$113 \pm 2.2(1\sigma) \mu\text{m}$
Uniformity map			

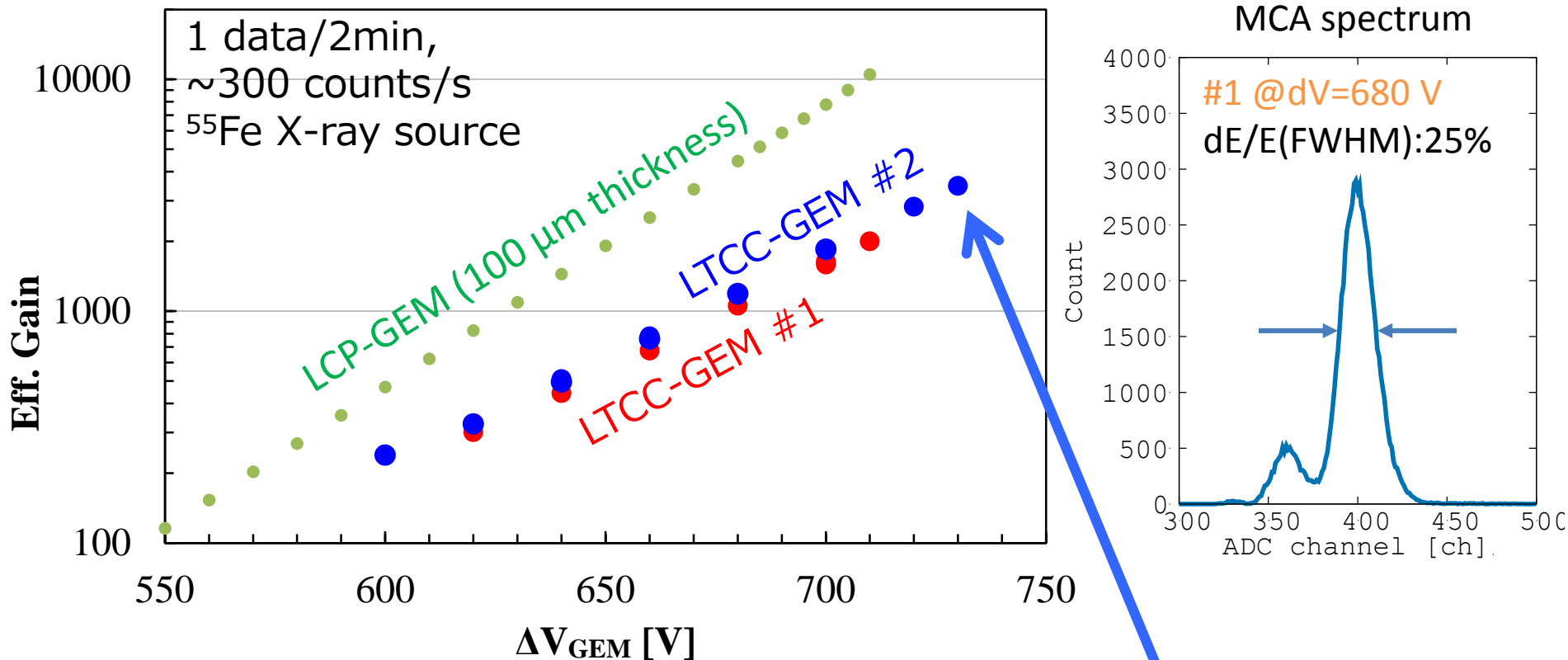
Comparing with design value,

- Hole diameter and pitch were formed within 3% error
- Thickness was controlled within 10% error

3-1. Experimental Setup

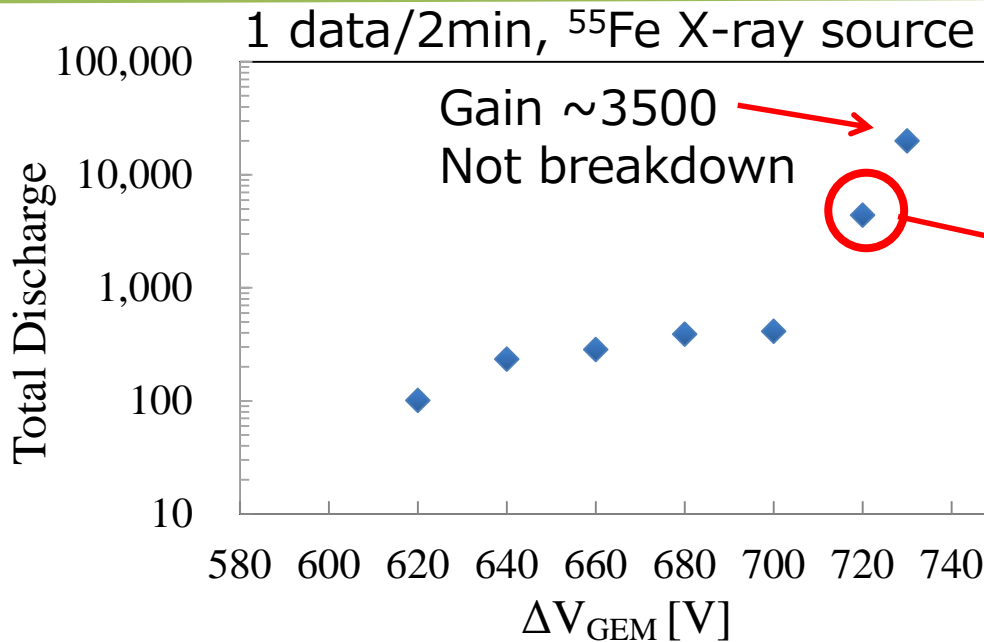


3-2. Gain curve



- The maximum gain was achieved approximately 3,500 at $dV_{\text{GEM}} = 730$ V.
- The energy resolution (FWHM) was obtained by 25%.

3-3. Number of discharges



Shaper output signal @ 720 V



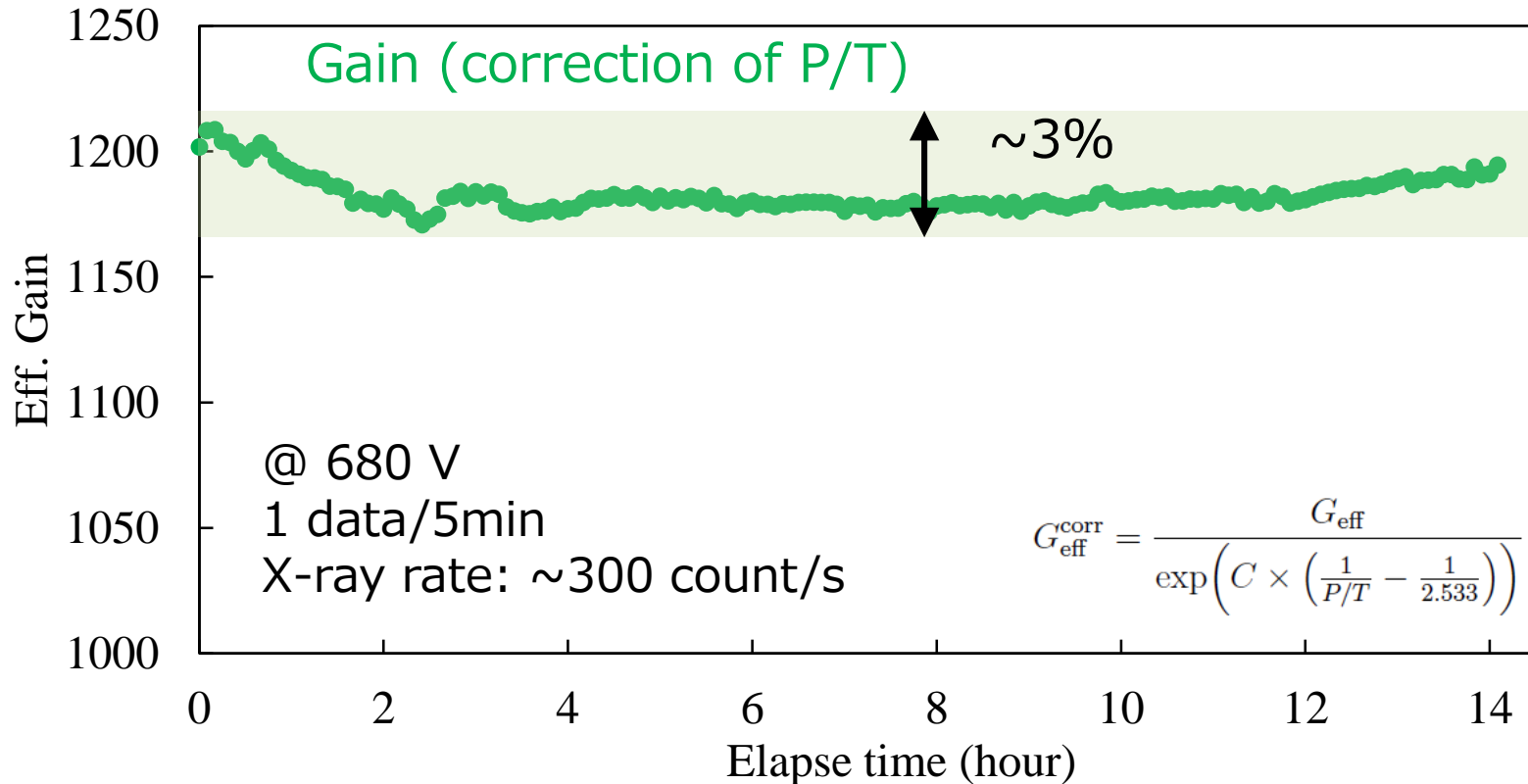
- We heard spark sounds from the chamber and watched flashes on GEM surface.
- Confirmed clear signals of X-ray after heavy discharge

Movie of discharges
top-view of GEM Eff. area



The LTCC-GEM was **NEVER broken** although it experienced more than 20,000 discharges at $dV=730\text{V}$.

3-4. Time stability



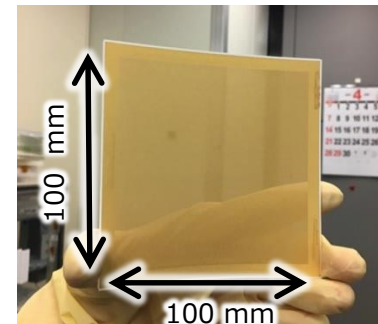
- The gain had a corrected pressure and temperature.
- We measured over 1,000 discharges during running data.
- The gain variation was 3% in 14 hours operation.

Excellent

Summary

✧ Succeed in fabrication of LTCC-GEM

- 100 mm × 100 mm size
- Using simple fabrication process
- Mechanical accuracy :
 - Hole size & pitch : Controlled under 3% error
 - Thickness : Controlled under 10% error



✧ Experiment results

- Maximum gain : $\sim 3,500$ at $dV_{\text{GEM}} = 730$ V
- Discharge tolerance : $> 20,000$ discharges, but no breakdown!
- Time stability (14 hours): gain variation $< 3\%$

Future plan

- ✧ Decrease discharge in operation
- ✧ Develop a sealed gas detector using LTCC-GEM
- ✧ Continue R&D with collaborators interested in LTCC-GEM

Thank you for your attention

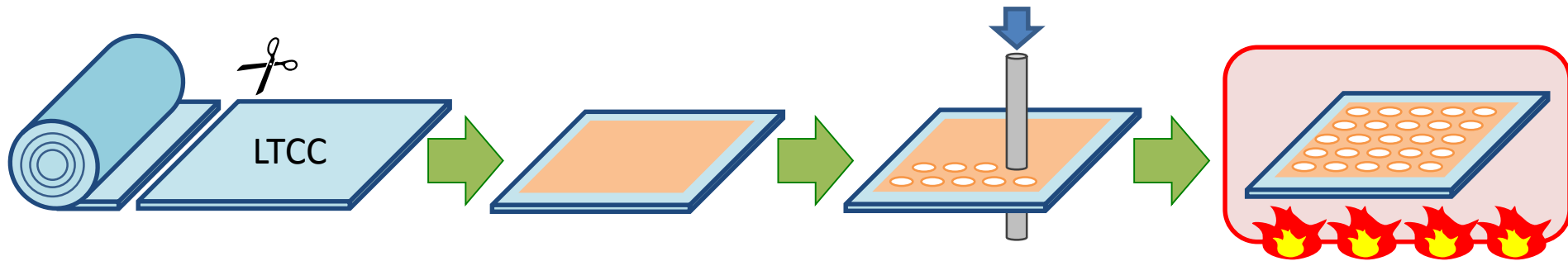


TIRI official mascot : TIRIN®

Back up

Plan of discharge prevention

Process



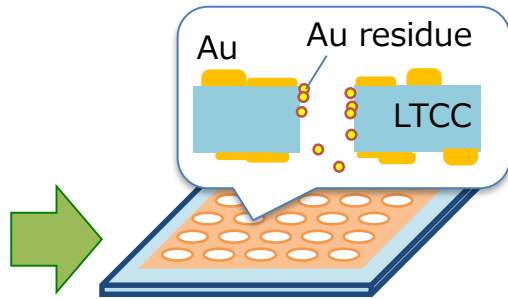
1. Cutting Green Sheet

2. Applying Au paste

3. Punching

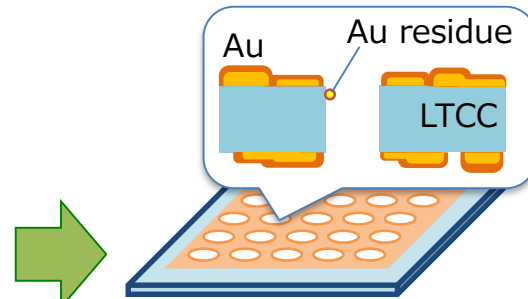
4. Sintering
($<1000^{\circ}\text{C}$)

Additional process for discharge prevention



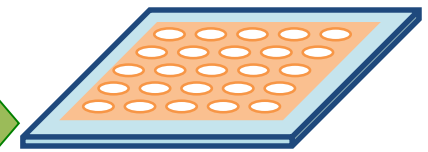
5. Etching

For removing Au residue
in the holes



6. Au non-electrolytic plating

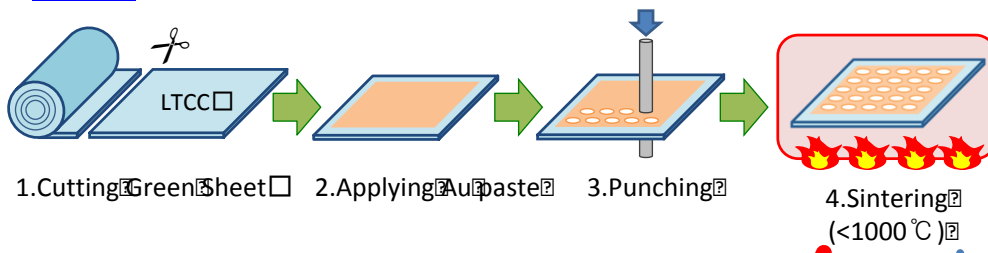
For recovering Au electrode
lost by etching



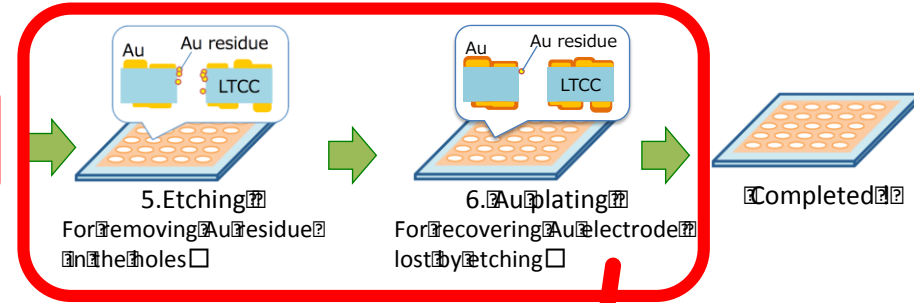
Completed !

Plan of discharge prevention -- SEM image --

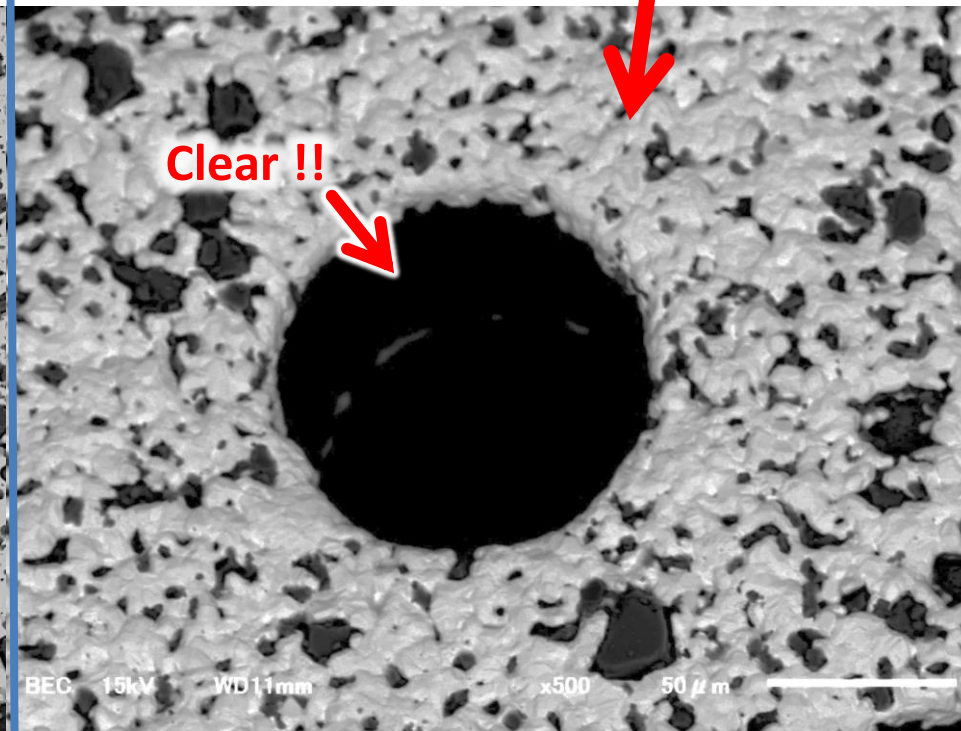
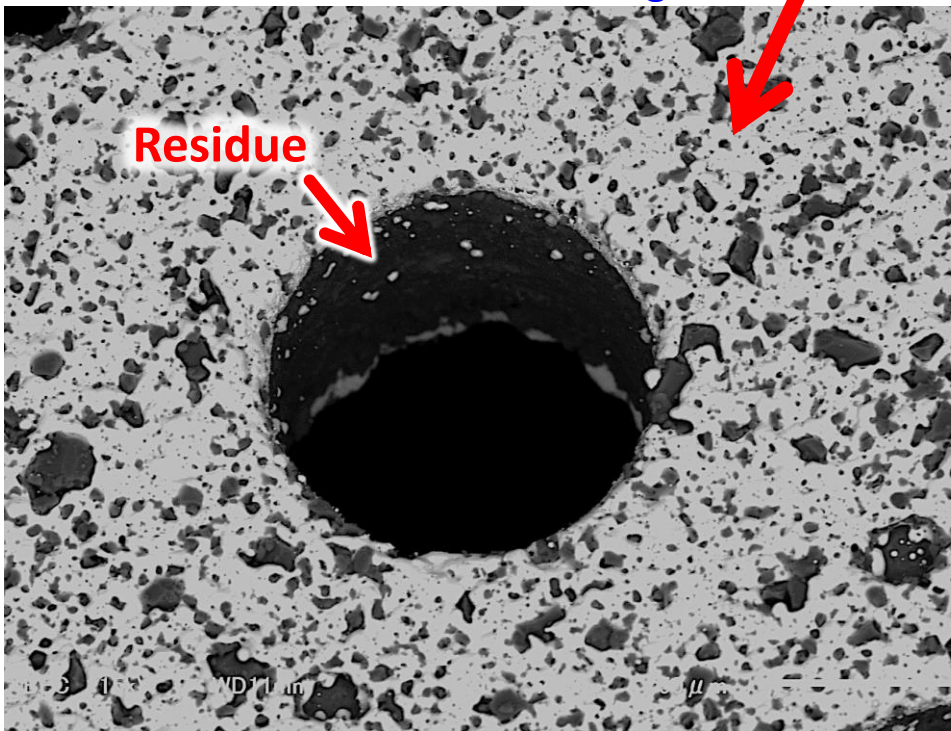
Process



Additional process for discharge prevention

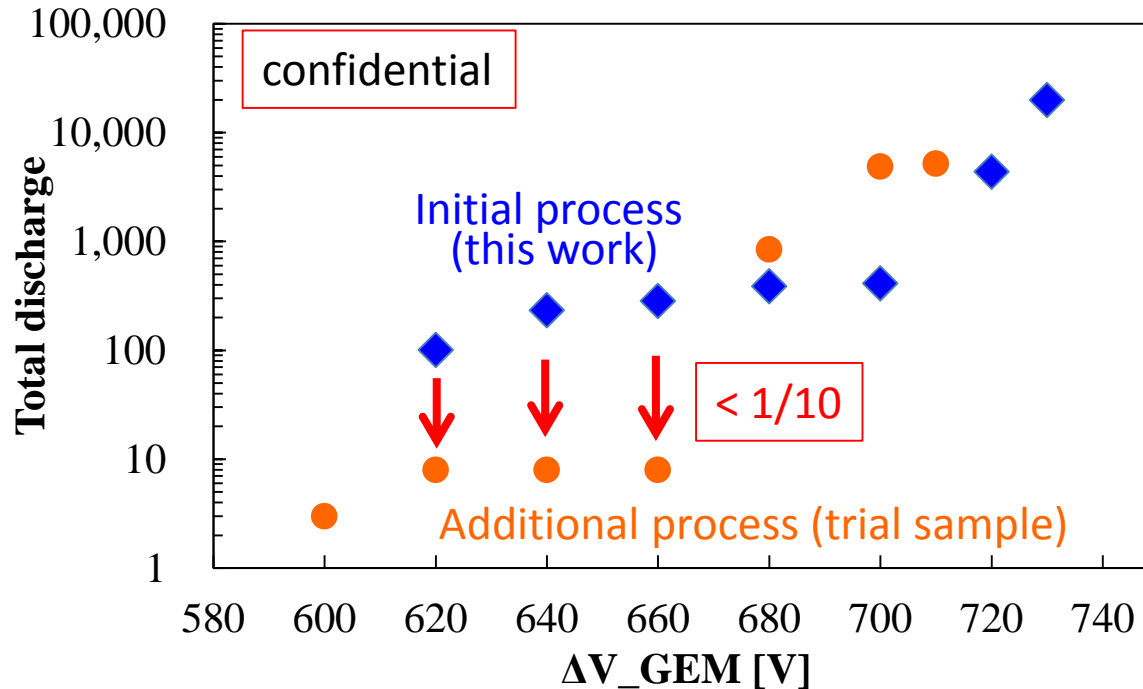
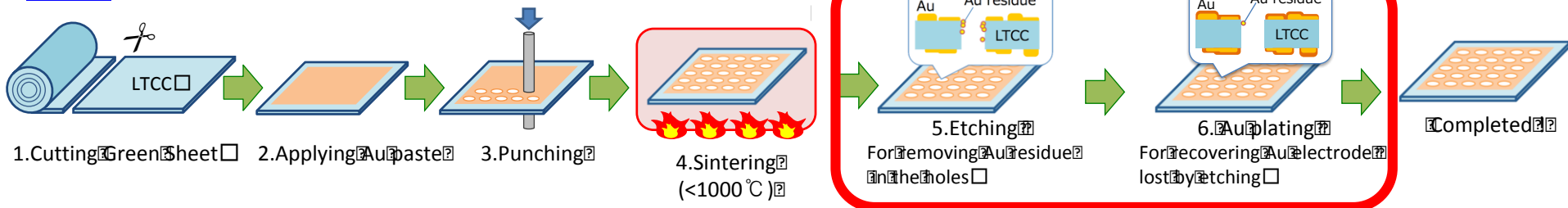


backscattered electron SEM image



Plan of discharge prevention -- test --

Process

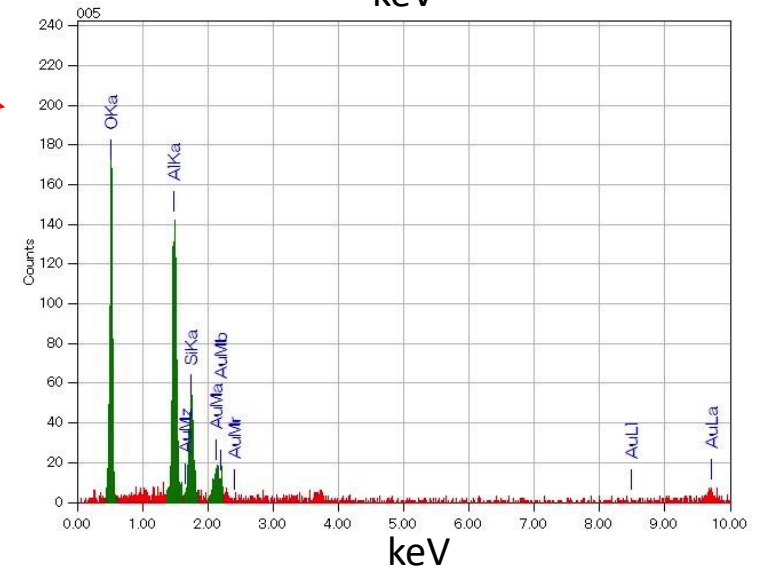
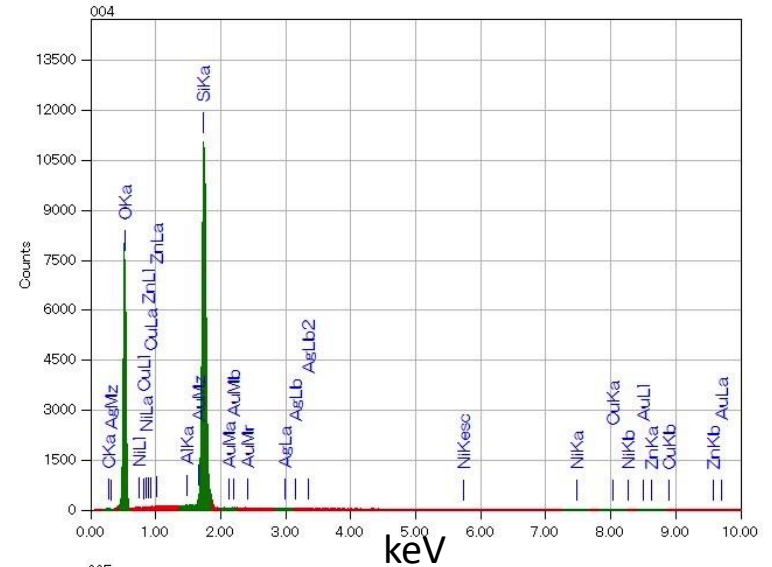
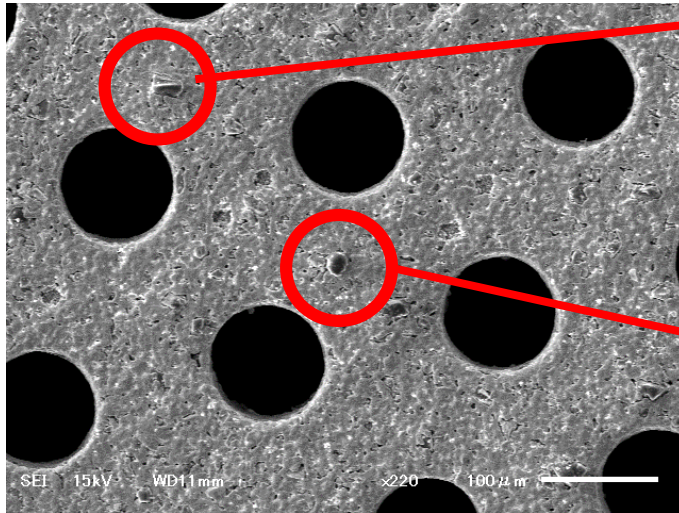


- ◆ At $\Delta V_{GEM} \leq 660$ V, discharges decrease using GEM of additional process.
- ◆ The process has effect.
- ◆ We must search optimum parameters of etching time and plating time in future work.

LTCC-GEM SEM-EDX analysis

EDX: Energy Dispersive X-ray

What is some clods put on LTCC-GEM?

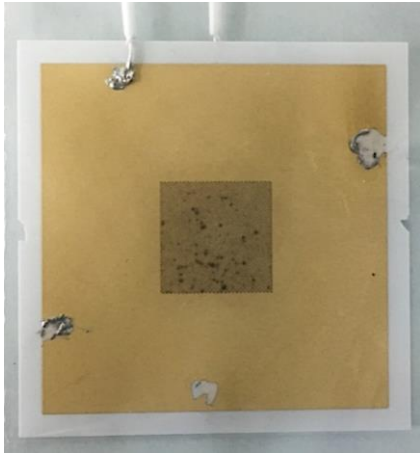


LTCC composition : Glass + Alumina
(CaO, SiO₂, B₂O₃ etc) (Al₂O₃)

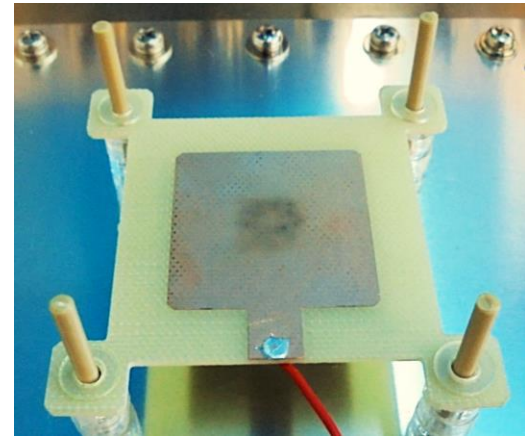
The clods is LTCC contained within Au paste.

Aging with discharge

- LTCC-GEM must need the aging with discharge to use without discharge.
- After aging, the weak points of discharge become non-discharge point.



After heavy discharges (aging)

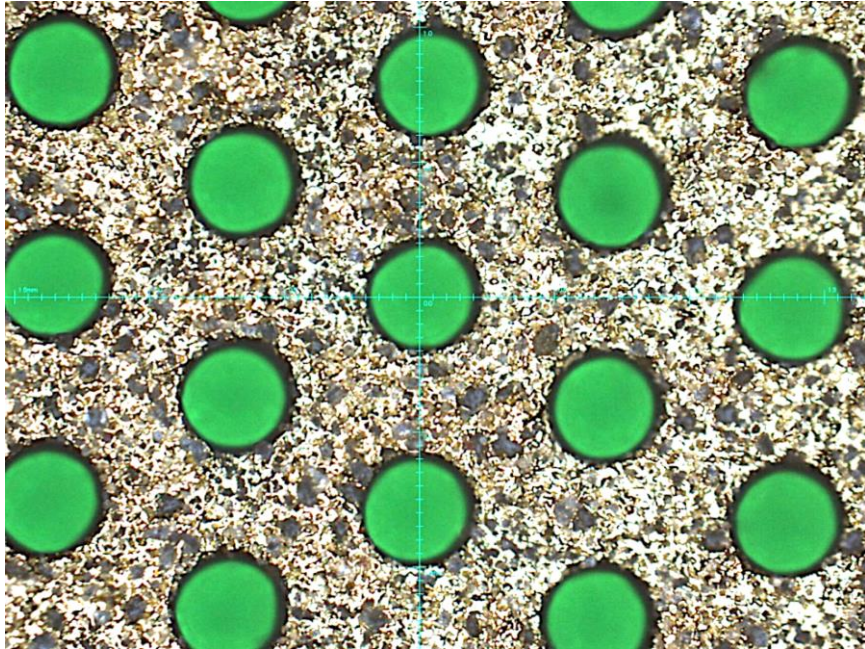


Contamination on readout pad

【problems】

- The contamination on readout pad and inside of chamber
- Troublesome task : essential aging before test

Spark tolerance



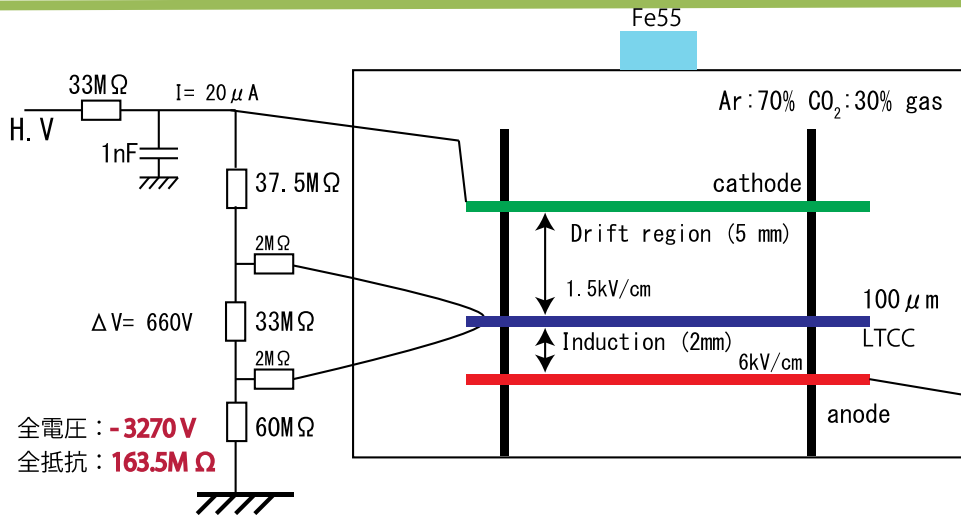
Before the experiment



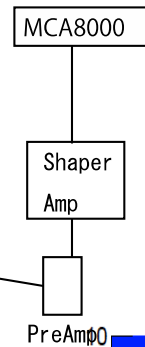
After the experiment
(Discharged part)

- Some burned print where observed around the hole, but no change of gas gain and energy resolution.
- LTCC substrate has a tolerance against sparks.

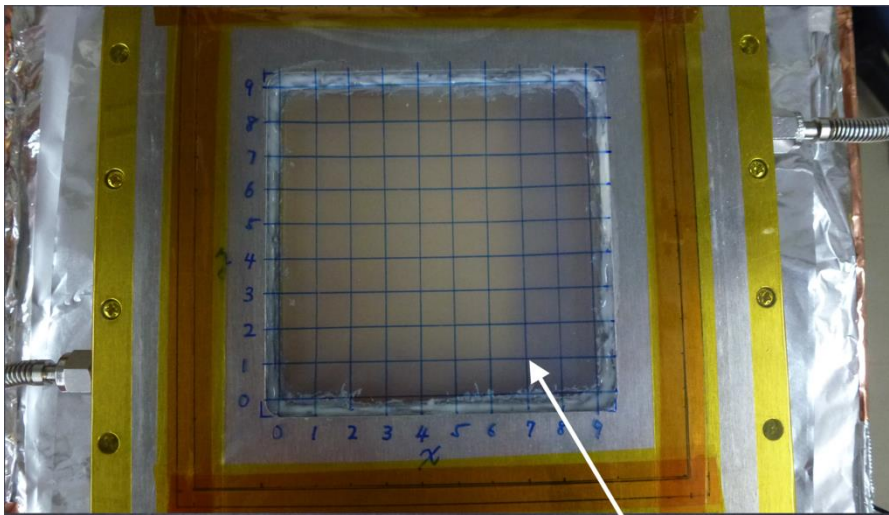
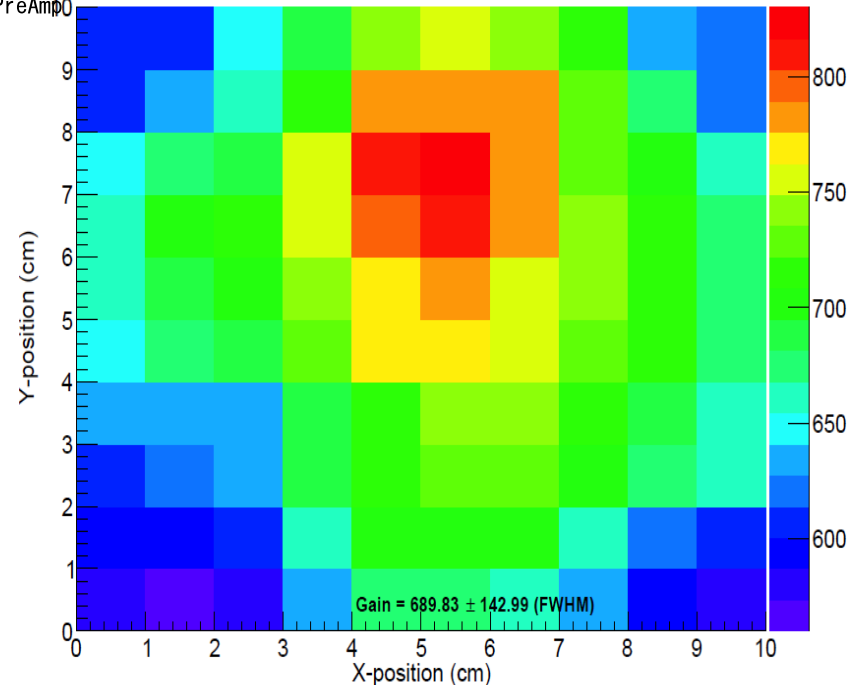
Gain uniformity



Measurement by Kato-san
(Kindai Univ., Japan)



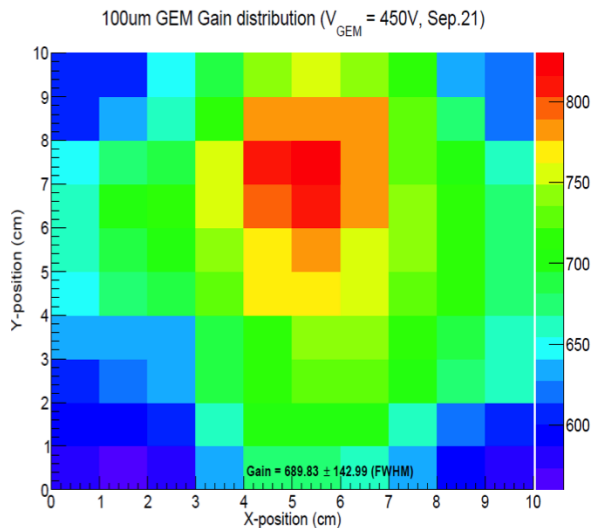
100um GEM Gain distribution ($V_{GEM} = 450V$, Sep.21)



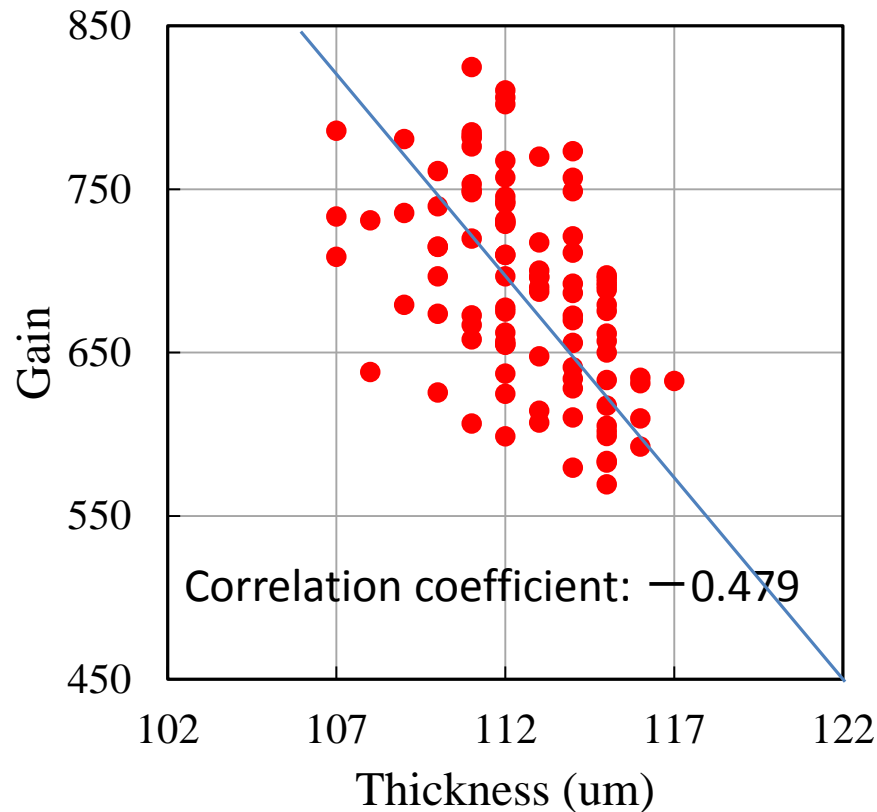
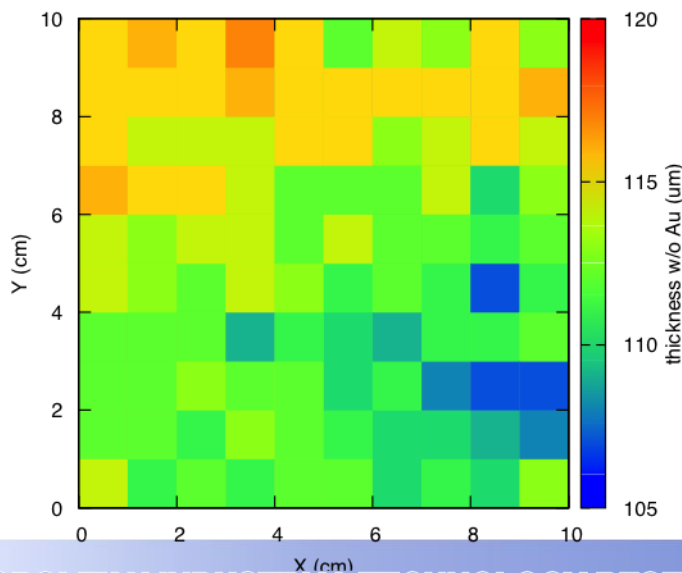
Put ⁵⁵Fe source on a cross point

Gain uniformity vs Thickness

Gain



Thickness



Loose correlation !!

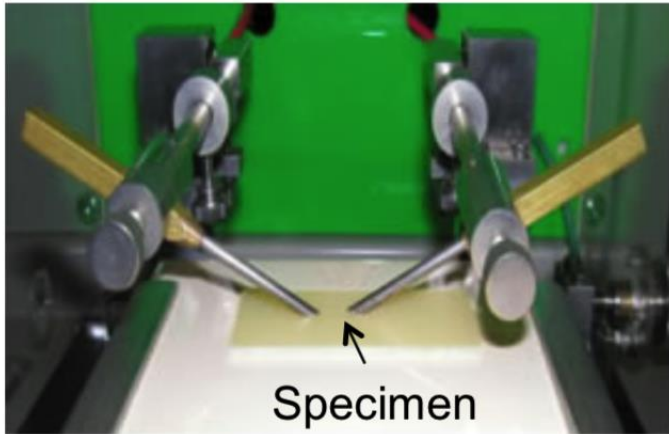
$$\text{Gain} = \exp(\alpha \cdot d) \quad \frac{\alpha}{P} = A \exp\left(-B \frac{P}{E}\right),$$

$$\Delta V_{GEM} = \text{const.}$$

If thickness is shorter, E-field & gain is higher.

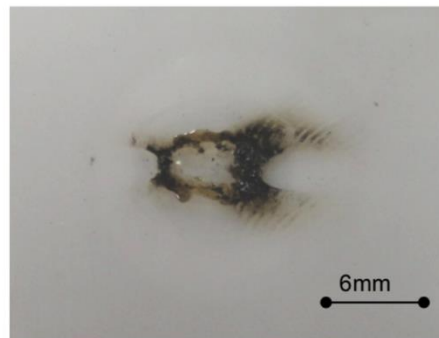
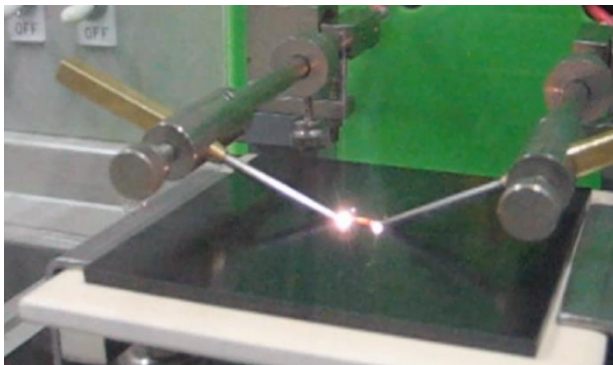
Arc resistance test

ASTM D495.

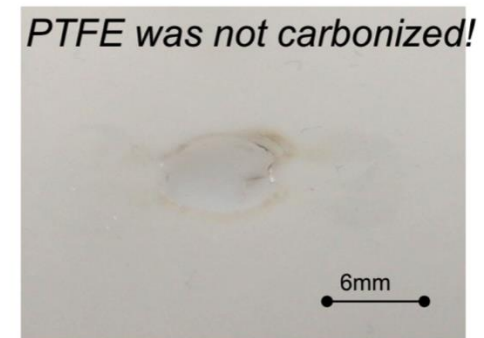


- Arc resistance is defined as the time period that a material resists the formation of a surface-conducting path.
- The test is carried out under the intermittently occurring arc of high voltage at low current characteristics.

Tungsten electrodes: 6.35 mm apart each other
Applied voltage: 12.5 kV



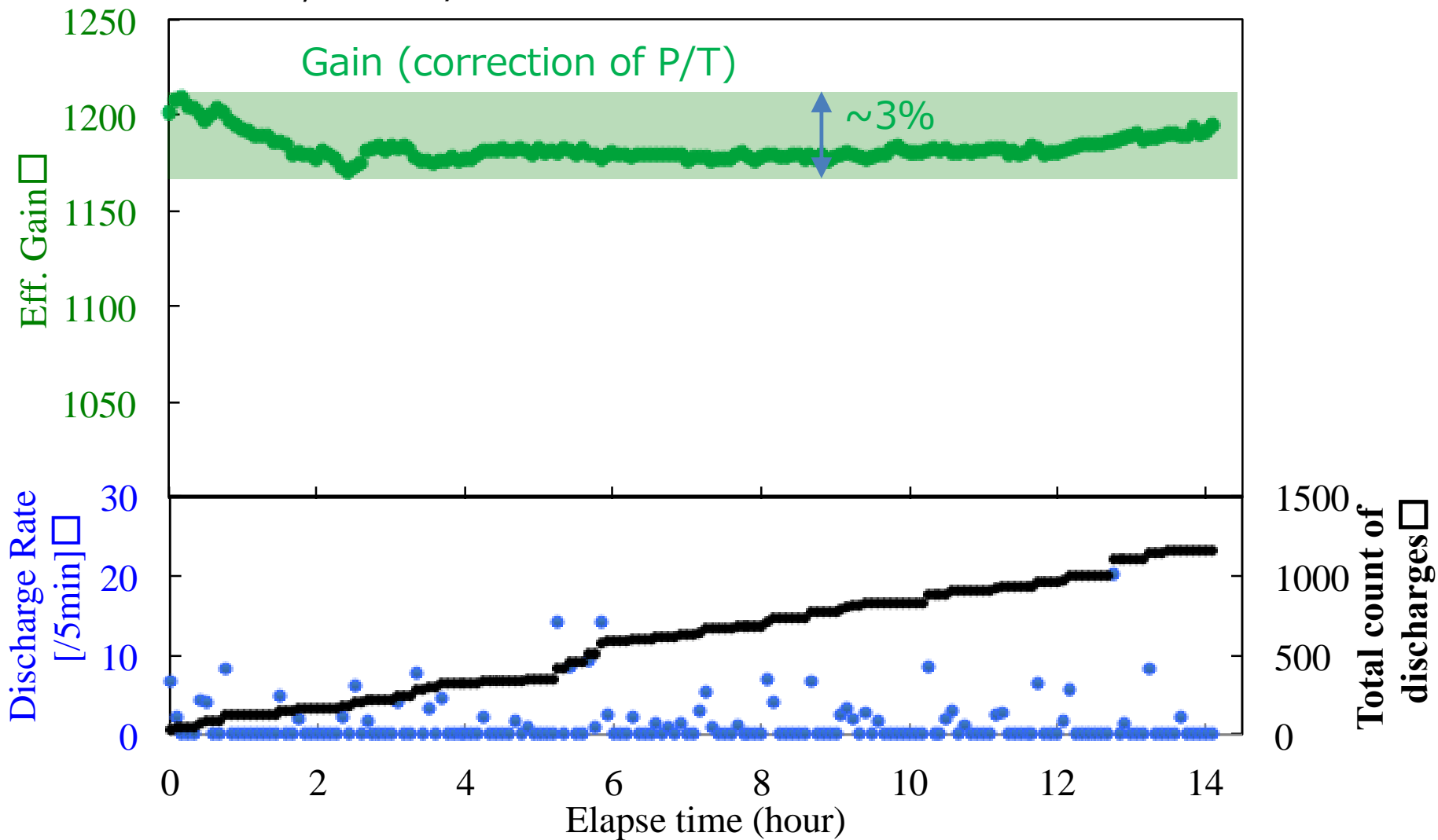
PET 82 s



PTFE >239 s

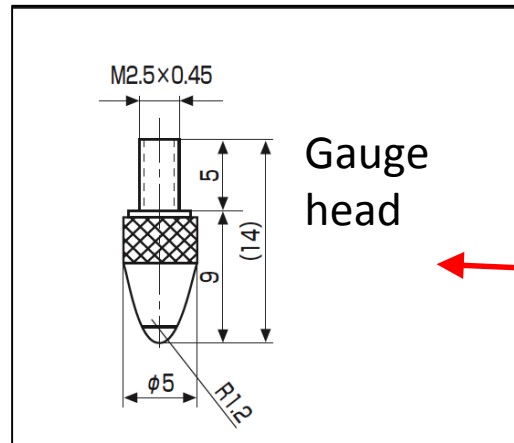
Time stability

@ 680 V, 1 data/5min



Measurement of LTCC-GEM thickness

- Contact type film thickness measuring gauge (Nikon Digimicro MFC-101)
- Measurement accuracy : 1 μ m

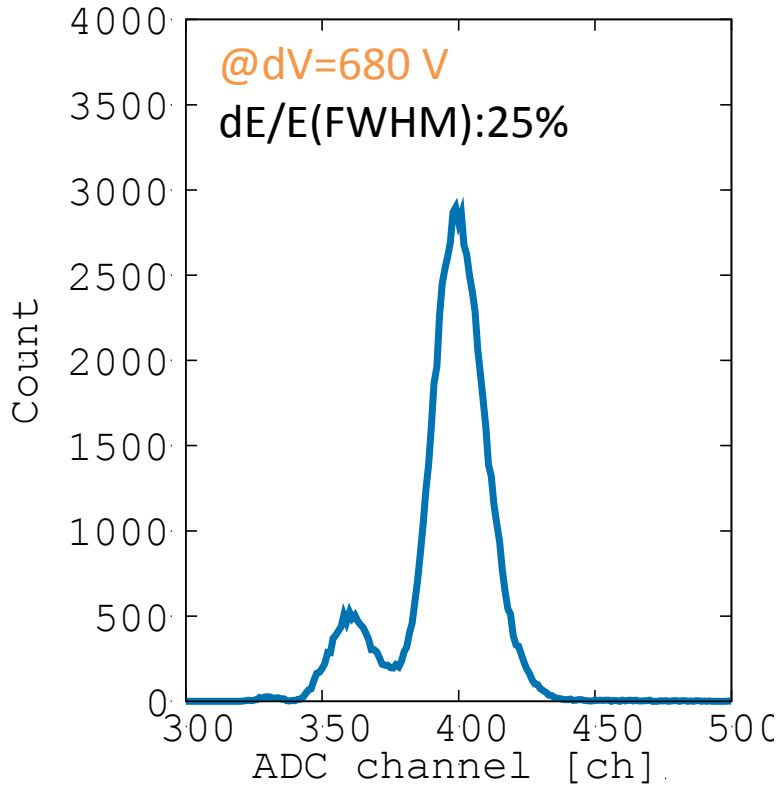


- Measured area : 100 points (10 x 10 points)
1cm step



MCA spectrum

MCA spectrum w/o discharge



MCA spectrum with discharges

